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DOCKET NO: VSEA 005-99

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Charles M. McKenna et al.  
Serial No: 09/602,059  
Confirmation No: 9493  
Filed: June 23, 2000  
For: ION IMPLANTER HAVING TWO-STAGE DECELERATION  
BEAMLINE  
Examiner: Mary A. El-Shammaa  
Art Unit: 2881

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The undersigned hereby certifies that this document is being placed in the United States mail with first-class postage attached, addressed to Commissioner for Patents, Washington, D.C. 20231, on the 6<sup>th</sup> day of May, 2003.

*Cheryl A. Putcell*  
Cheryl Putcell

Commissioner for Patents  
Washington, D.C. 20231

Sir:

AMENDMENT

In response to the Office Action mailed November 6, 2002, please amend the above-identified application as follows.

In the Claims

Please amend claims 1, 15, 30, 37, 45 and 52 to read as follows. Marked-up copies of the amended claims, with changes indicated by bracketing and underlining, are enclosed.

1. (As Amended) An ion implanter comprising:

A<sup>1</sup>  
an ion source for generating an ion beam at a first voltage  $V_0$ ;  
an analyzer for separating unwanted components from said ion beam;  
a beam transport device for transporting said ion beam through said  
analyzer at a first transport energy;